

Etching Method

ABSTRACT

The electromagnetic induction window (2), a part of or the entire wall of the etching chamber (1) which is in contact with plasma, and other elements within the etching chamber (1) are constructed of a material of which composition ratio of oxygen is 50% or less, in particular silicon nitride, or other materials such as silicon, silicon carbonate, carbon, aluminum nitride, polyimide, and polyamide.

10 (Figure 1)